IN THE CLAIMS

Please amend the claims as follows:

1. (Canceled)

2. (Canceled)

3. (Canceled)

4 – 52 (Canceled)

53. (Canceled)

54. (Canceled)

55. (Currently Amended) A surfactant-templated mesoporous dielectric film on a substrate prepared by evaporation from silica precursors ~~having greater than eight carbon atoms for every one silica atom and~~ a surfactant wherein such film is characterized by:

greater than eight carbon atoms for every one silica atom;

a dielectric constant less than 3.0 that is stable, wherein a stable film has at least one of either relative stability, wherein a dielectric constant increases no more than approximately 20% when the film is taken from an equilibrated condition of 0.0% relative humidity or vacuum to an equilibrated condition of 50% relative humidity, or absolute stability, wherein the dielectric constant remains less than 3 under any conditions including humid conditions of at least 40% relative humidity;

a film thickness from about 0.1 μm to about 1.5 μm; and

an average pore diameter less than or equal to about 20 nm.

57 – 74 (Canceled)

75. (Currently Amended) A surfactant-templated mesoporous dielectric film on a substrate prepared from a silica precursor solution by evaporation, wherein the film is characterized by disordered porosity, lacking a regular geometric arrangement of pores, and characterized by absence of an x-ray diffraction peak in the range of 2-6 [degress 2-theta;] degrees 2-theta having greater than eight carbon atoms for every 1 silica atom.

76. (Previously Presented) The dielectric film of claim 75, wherein the silica precursor solution includes one or more of methyl and ethyl groups.

77. (Previously Presented) The dielectric film of claim 75, wherein the silica precursor solution includes one or more of alkyl and phenyl groups.

78. (Canceled)

79 - 92 (Canceled)